

ABSTRACT

SHADOW MASK AND BASE MATERIAL THEREFOR

A high-definition shadow mask, including a stretched mask, and a base material for a shadow mask, wherein the center line average roughness R_a of the small aperture-side surface is not more than $0.25\text{ }\mu\text{m}$, and the center line average roughness R_a of the large aperture-side surface is larger than the center line average roughness R_a of the small aperture-side surface by at least $0.25\text{ }\mu\text{m}$ and is not larger than $1\text{ }\mu\text{m}$.

Figure : None